
CSE477

VLSI Digital Circuits

Fall 2002

Lecture 02: Design Metrics

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[Adapted from Rabaey's *Digital Integrated Circuits*, ©2002, J. Rabaey et al.]

Course Administration

- ❑ Instructor: Mary Jane Irwin
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Office Hrs: W & R 17:30 to 19:30 in 101 Pond
- ❑ Labs: Accounts on 101 Pond Lab machines
- ❑ URL: www.cse.psu.edu/~cg477
- ❑ Text: *Digital Integrated Circuits*, 2nd Edition
Rabaey et. al., ©2002 (October)
- ❑ Handouts: Leftover handouts available outside my office
door after class

Grading Information

□ Grade determinates

- Midterm Exam ~25%
 - Wednesday, **October 16th**, 20:15 to 22:15, 260 Willard
- Final Exam ~25%
 - Monday, December 16th, 10:10 to noon, Location TBD
- Homeworks/Lab Assignments (5) ~20%
 - Due at the beginning of class (or, if submitted electronically, by 17:00 on the due date). **No late** assignments will be accepted.
- Design Project (teams of ~2) ~25%
- In-class pop quizzes ~ 5%

□ Please let me know about exam conflicts **ASAP**

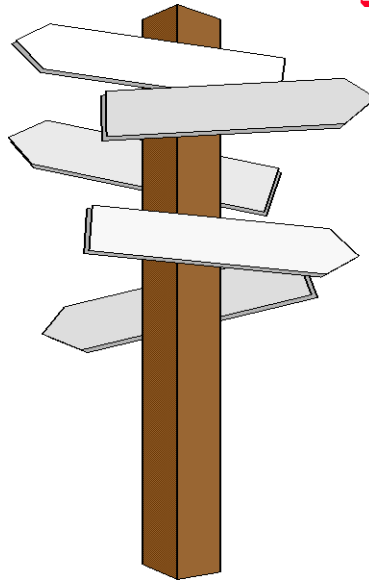
□ Grades will be posted on the course homepage

- December 10th **deadline** for filing grade updates via email

Major Design Challenges

□ Microscopic issues

- ultra-high speeds
- power dissipation and supply rail drop
- growing importance of interconnect
- noise, crosstalk
- reliability, manufacturability
- clock distribution



□ Macroscopic issues

- time-to-market
- design complexity (millions of gates)
- high levels of abstractions
- design for test
- reuse and IP, portability
- systems on a chip (SoC)
- tool interoperability

Year	Tech.	Complexity	Frequency	3 Yr. Design Staff Size	Staff Costs
1997	0.35	13 M Tr.	400 MHz	210	\$90 M
1998	0.25	20 M Tr.	500 MHz	270	\$120 M
1999	0.18	32 M Tr.	600 MHz	360	\$160 M
2002	0.13	130 M Tr.	800 MHz	800	\$360 M

Overview of Last Lecture

- ❑ Digital integrated circuits experience exponential growth in complexity (Moore's law) and performance
- ❑ Design in the deep submicron (DSM) era creates new challenges
 - ❑ Devices become somewhat different
 - ❑ Global clocking becomes more challenging
 - ❑ Interconnect effects play a more significant role
 - ❑ Power dissipation may be *the* limiting factor
- ❑ Our goal in this class will be to understand and design digital integrated circuits in the deep submicron era
- ❑ Today we look at some basic design metrics

Fundamental Design Metrics

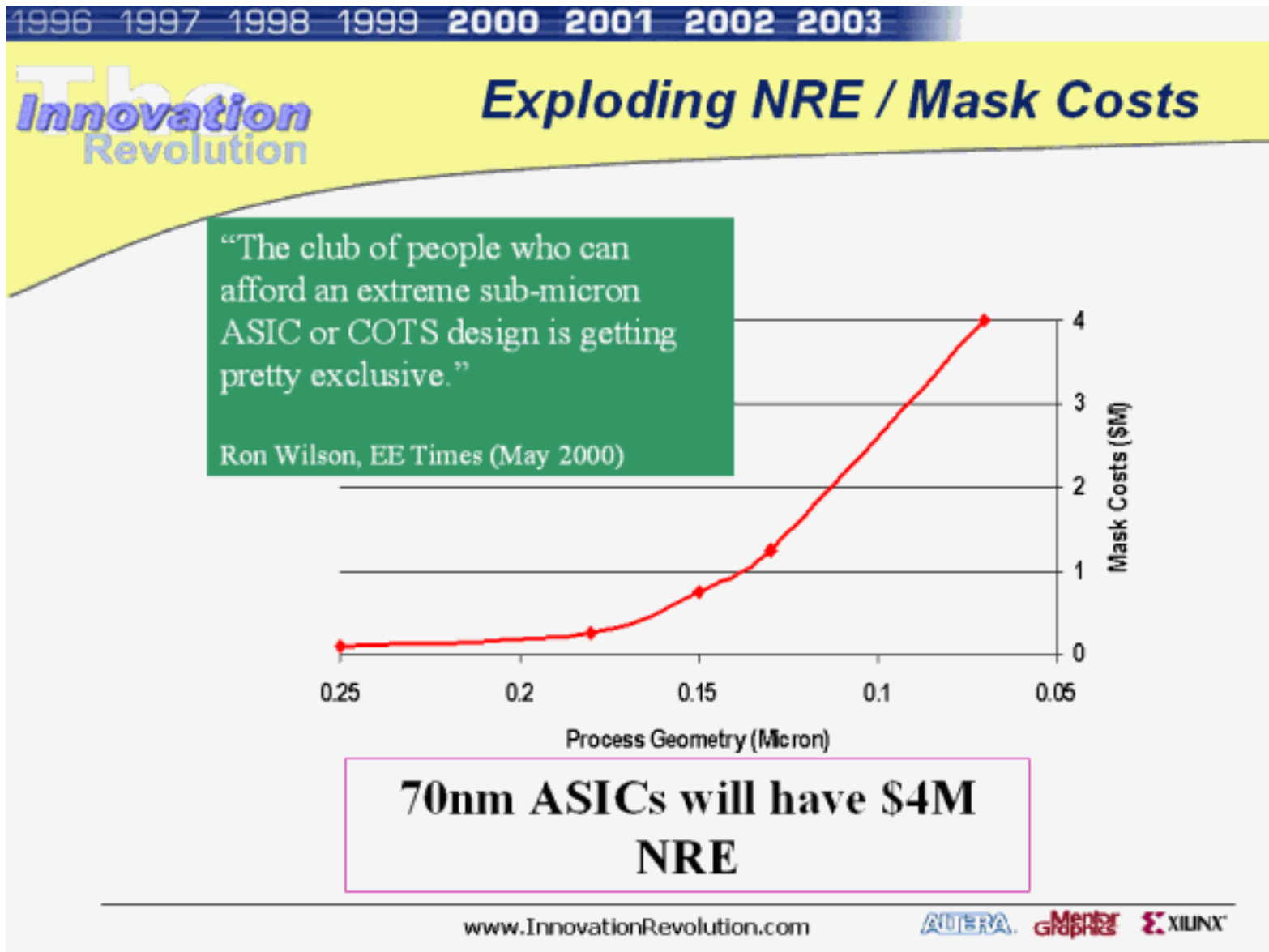
- ❑ Functionality
- ❑ Cost
 - ❑ NRE (fixed) costs - design effort
 - ❑ RE (variable) costs - cost of parts, assembly, test
- ❑ Reliability, robustness
 - ❑ Noise margins
 - ❑ Noise immunity
- ❑ Performance
 - ❑ Speed (delay)
 - ❑ Power consumption; energy
- ❑ Time-to-market

Cost of Integrated Circuits

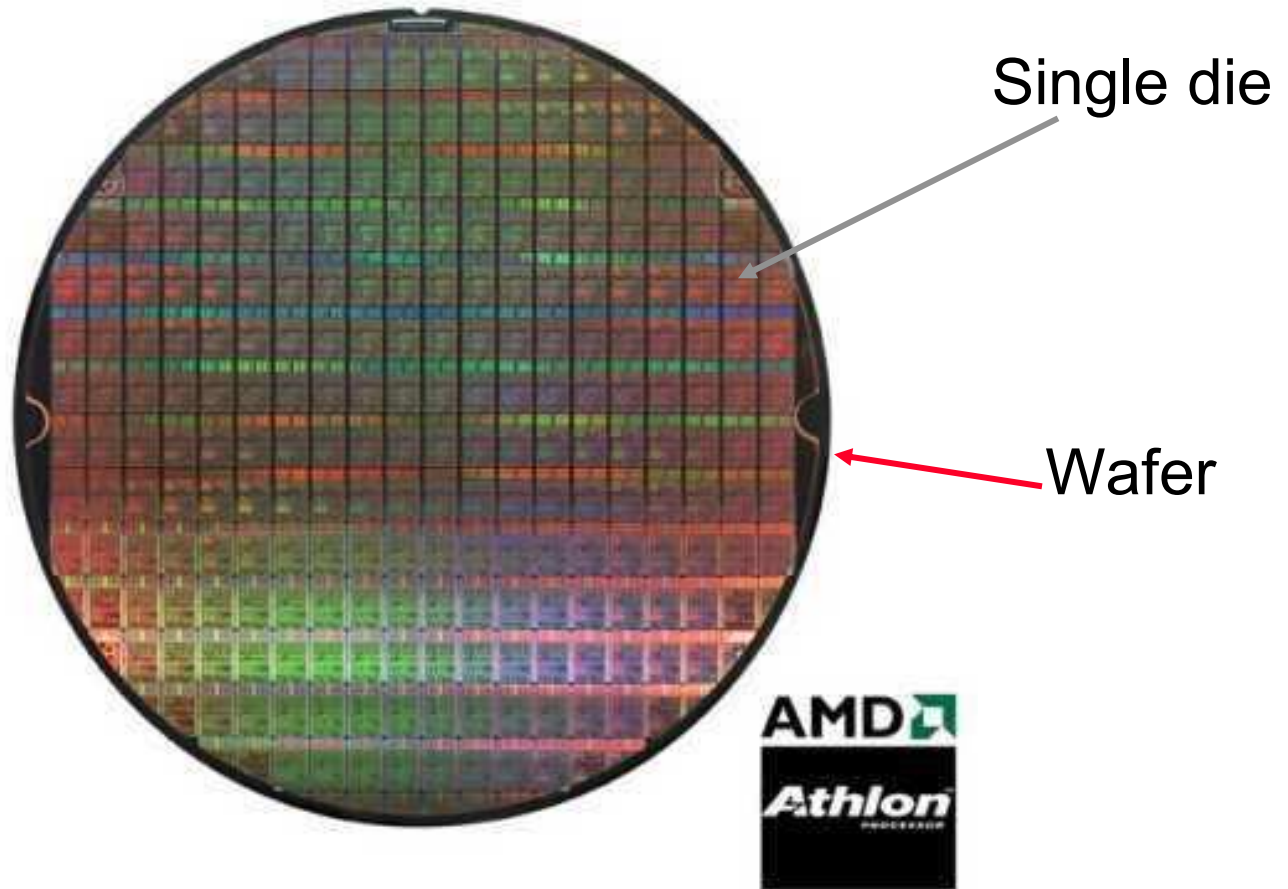
- ❑ NRE (non-recurring engineering) costs
 - ❑ Fixed cost to produce the design
 - design effort
 - design verification effort
 - mask generation
 - ❑ Influenced by the design complexity and designer productivity
 - ❑ More pronounced for small volume products
- ❑ Recurring costs – proportional to product volume
 - ❑ silicon processing
 - also proportional to chip area
 - ❑ assembly (packaging)
 - ❑ test

$$\text{cost per IC} = \text{variable cost per IC} + \frac{\text{fixed cost}}{\text{volume}}$$

NRE Cost is Increasing



Silicon Wafer



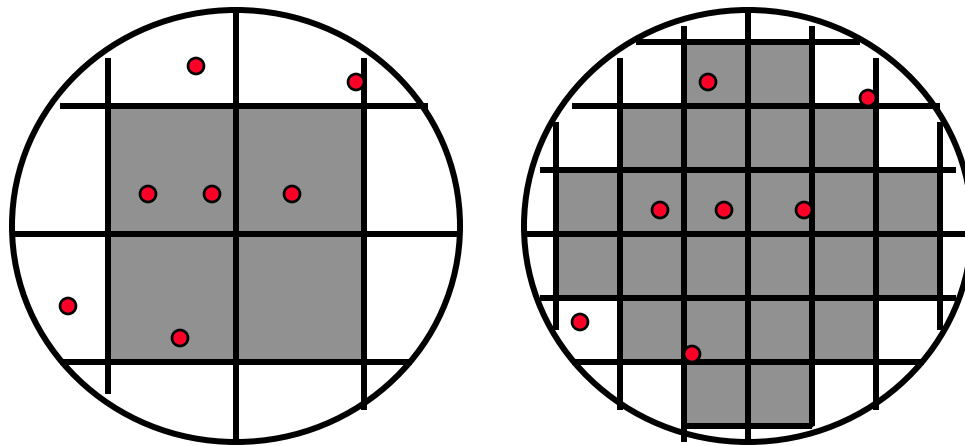
From <http://www.amd.com>

Recurring Costs

$$\text{variable cost} = \frac{\text{cost of die} + \text{cost of die test} + \text{cost of packaging}}{\text{final test yield}}$$

$$\text{cost of die} = \frac{\text{cost of wafer}}{\text{dies per wafer} \tilde{\alpha} \text{ die yield}}$$

$$\text{dies per wafer} = \frac{\pi \tilde{\alpha} (\text{wafer diameter}/2)^2}{\text{die area}} - \frac{\pi \tilde{\alpha} \text{ wafer diameter}}{\sqrt{2} \tilde{\alpha} \text{ die area}}$$



$$\text{die yield} = (1 + (\text{defects per unit area} \tilde{\alpha} \text{ die area})/\alpha)^{-\alpha}$$

Yield Example

❑ Example

- ❑ wafer size of 12 inches, die size of 2.5 cm^2 , 1 defects/ cm^2 , $\alpha = 3$ (measure of manufacturing process complexity)
- ❑ 252 dies/wafer (remember, wafers round & dies square)
- ❑ die yield of 16%
- ❑ $252 \times 16\% = \text{only } 40 \text{ dies/wafer die yield !}$

❑ Die cost is strong function of die area

- proportional to the third or fourth power of the die area

Examples of Cost Metrics (1994)

Chip	Metal layers	Line width	Wafer cost	Defects /cm ²	Area (mm ²)	Dies/wafer	Yield	Die cost
386DX	2	0.90	\$900	1.0	43	360	71%	\$4
486DX2	3	0.80	\$1200	1.0	81	181	54%	\$12
PowerPC 601	4	0.80	\$1700	1.3	121	115	28%	\$53
HP PA 7100	3	0.80	\$1300	1.0	196	66	27%	\$73
DEC Alpha	3	0.70	\$1500	1.2	234	53	19%	\$149
Super SPARC	3	0.70	\$1700	1.6	256	48	13%	\$272
Pentium	3	0.80	\$1500	1.5	296	40	9%	\$417

Reliability

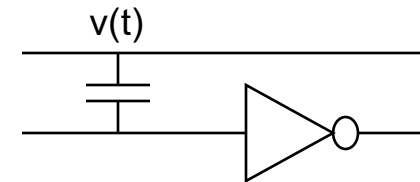
Noise in Digital Integrated Circuits

❑ **Noise** – unwanted variations of voltages and currents at the logic nodes

❑ from two wires placed side by side

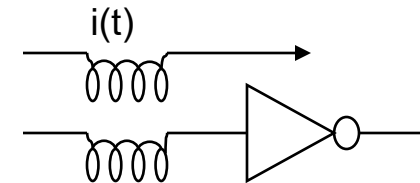
❑ **capacitive coupling**

- voltage change on one wire can influence signal on the neighboring wire
- cross talk



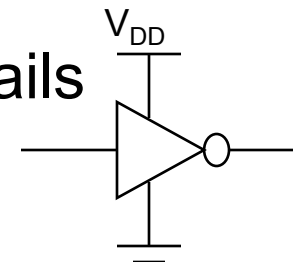
❑ **inductive coupling**

- current change on one wire can influence signal on the neighboring wire



❑ from noise on the power and ground supply rails

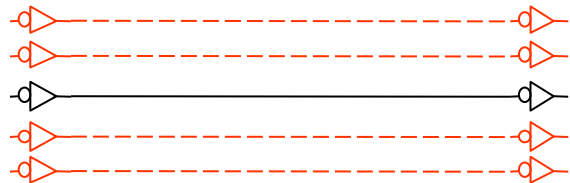
❑ can influence signal levels in the gate



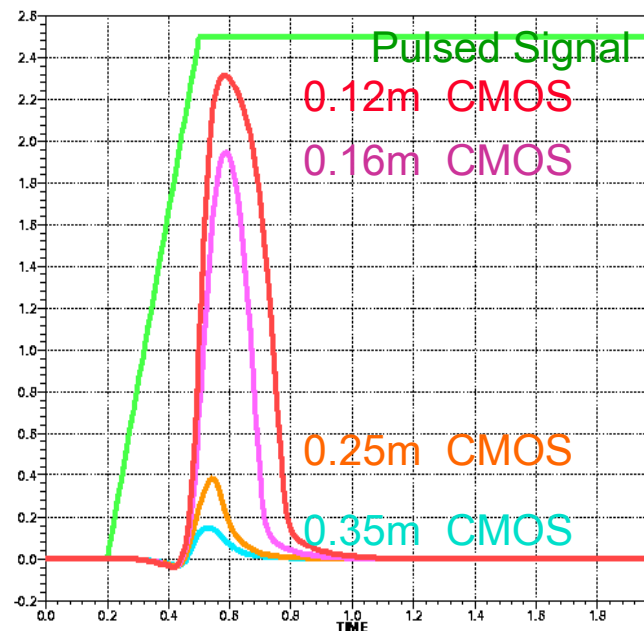
Example of Capacitive Coupling

- ❑ Signal wire glitches as large as 80% of the supply voltage will be common due to crosstalk between neighboring wires as feature sizes continue to scale

Crosstalk vs. Technology



Black line quiet —————
Red lines pulsed - - - - -
Glitches strength vs technology

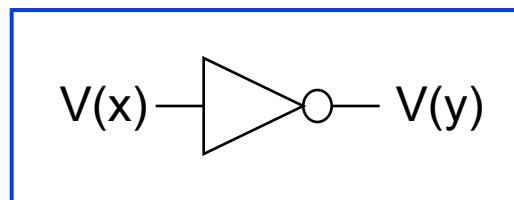


From Dunlop, Lucent, 2000

Static Gate Behavior

- ❑ Steady-state parameters of a gate – *static behavior* – tell how robust a circuit is with respect to both variations in the manufacturing process and to noise disturbances.
- ❑ Digital circuits perform operations on Boolean variables $x \in \{0,1\}$
- ❑ A logical variable is associated with a *nominal voltage level* for each logic state

$$1 \Leftrightarrow V_{OH} \text{ and } 0 \Leftrightarrow V_{OL}$$



$$V_{OH} = ! (V_{OL})$$

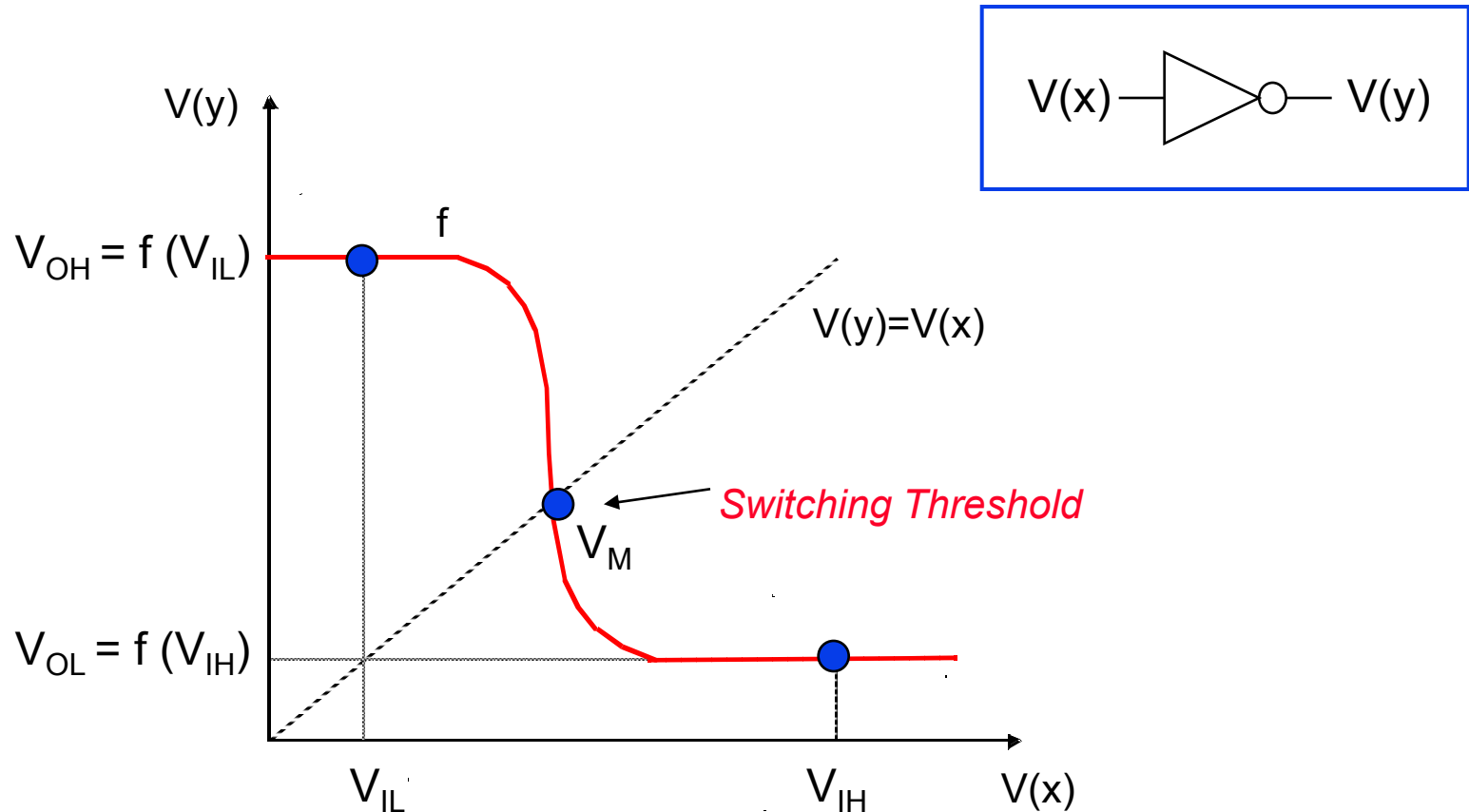
$$V_{OL} = ! (V_{OH})$$

- ❑ Difference between V_{OH} and V_{OL} is the *logic* or *signal swing* V_{sw}

DC Operation

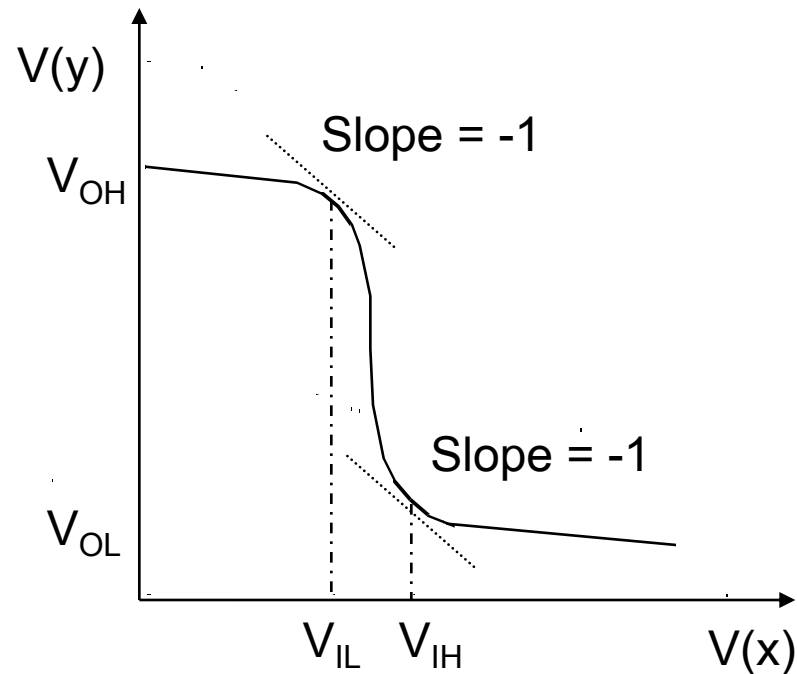
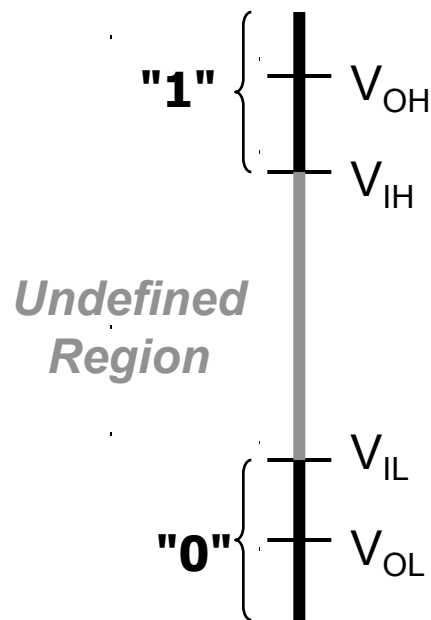
Voltage Transfer Characteristics (VTC)

- Plot of output voltage as a function of the input voltage



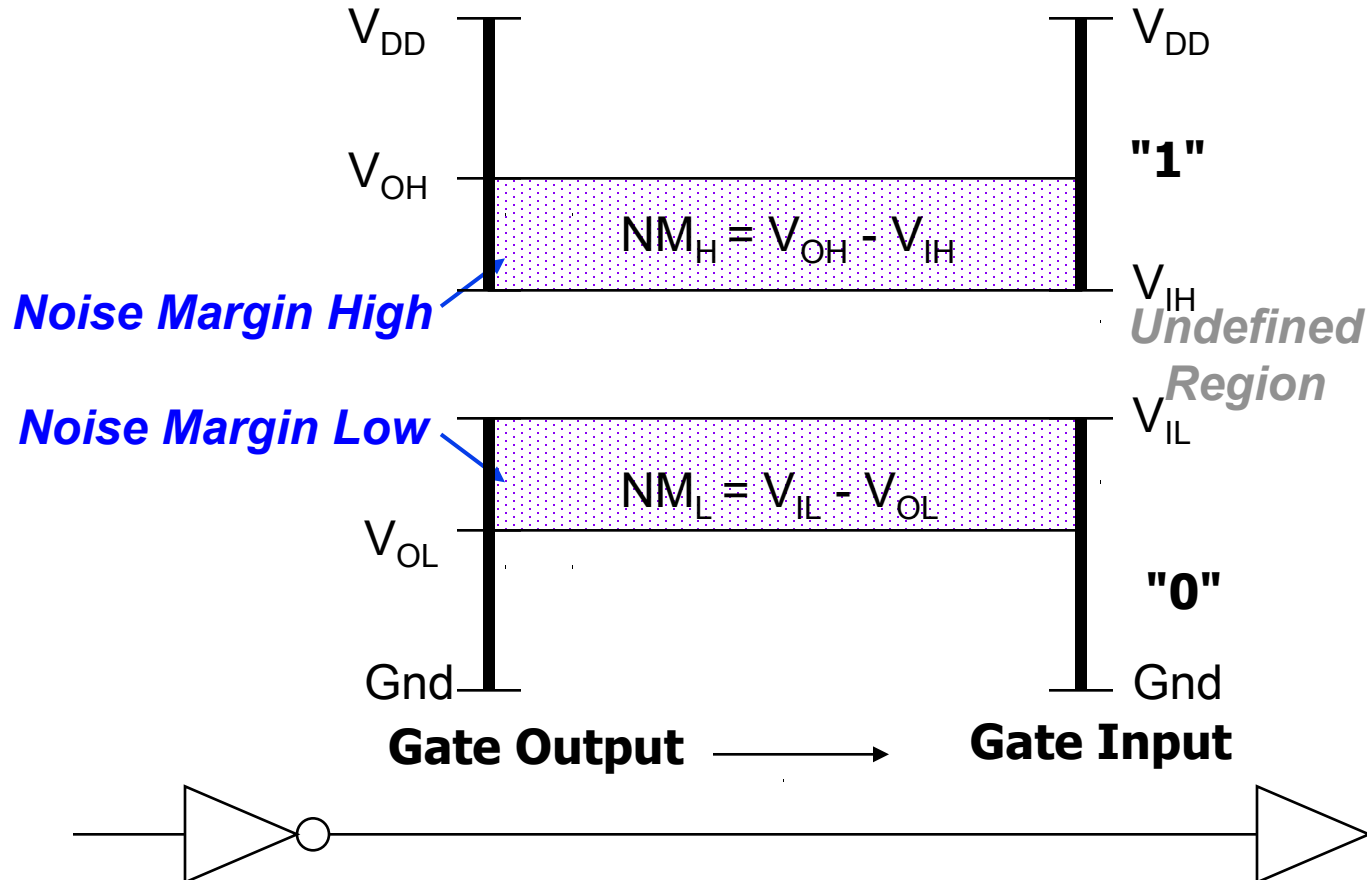
Mapping Logic Levels to the Voltage Domain

- ❑ The regions of acceptable high and low voltages are delimited by V_{IH} and V_{IL} that represent the points on the VTC curve where the gain = -1



Noise Margins

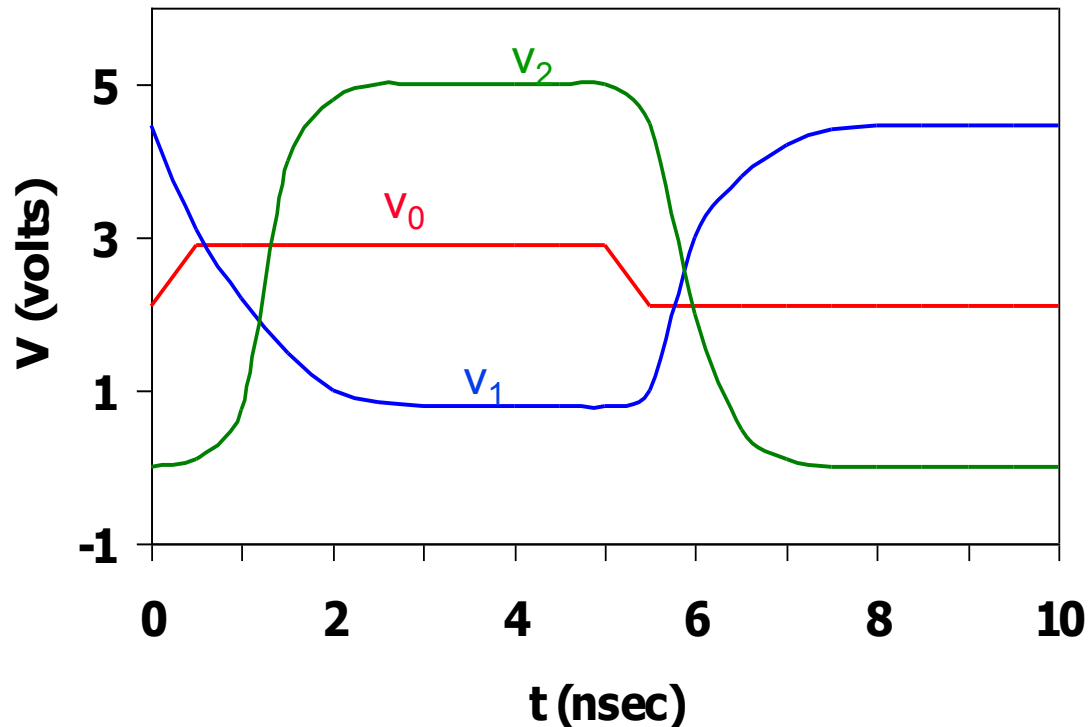
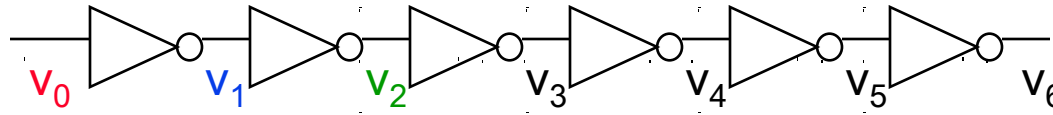
- For robust circuits, want the “0” and “1” intervals to be as large as possible



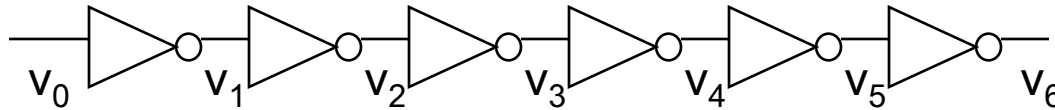
- Large noise margins are desirable, but not sufficient ...

The Regenerative Property

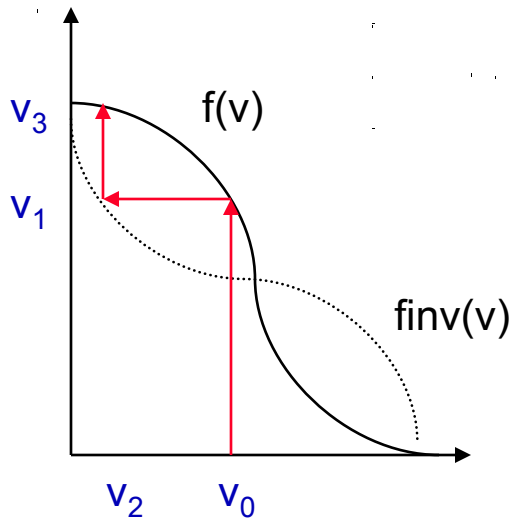
- ❑ A gate with regenerative property ensure that a disturbed signal converges back to a nominal voltage level



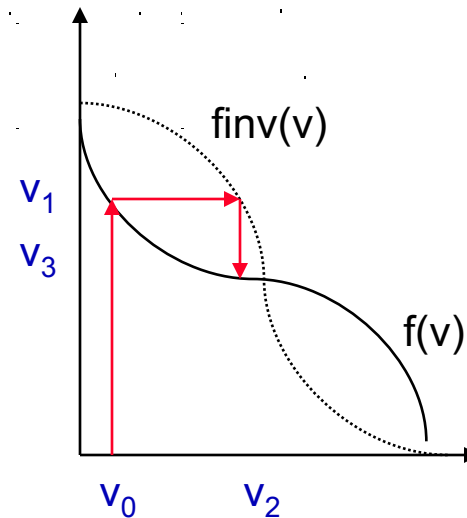
Conditions for Regeneration



$$v_1 = f(v_0) \Rightarrow v_1 = \text{finv}(v_2)$$



Regenerative Gate



Nonregenerative Gate

- ❑ To be regenerative, the VTC must have a transient region with a gain **greater** than 1 (in absolute value) bordered by two valid zones where the gain is **smaller** than 1. Such a gate has two stable operating points.

Noise Immunity

- ❑ Noise margin expresses the ability of a circuit to overpower a noise source
 - ❑ noise sources: supply noise, cross talk, interference, offset
- ❑ Absolute noise margin values are deceptive
 - ❑ a floating node is more easily disturbed than a node driven by a low impedance (in terms of voltage)
- ❑ *Noise immunity* expresses the ability of the system to process and transmit information correctly in the presence of noise
- ❑ For good noise immunity, the signal swing (i.e., the difference between V_{OH} and V_{OL}) and the noise margin have to be large enough to overpower the impact of fixed sources of noise

Directivity

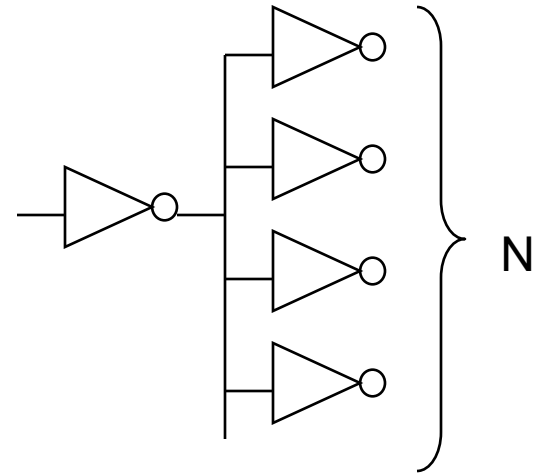
- ❑ A gate must be *undirectional*: changes in an output level should not appear at any unchanging input of the same circuit
 - ❑ In real circuits *full* directivity is an illusion (e.g., due to capacitive coupling between inputs and outputs)

- ❑ Key metrics: *output impedance* of the driver and *input impedance* of the receiver
 - ❑ ideally, the output impedance of the driver should be zero
 - ❑ input impedance of the receiver should be infinity

Fan-In and Fan-Out

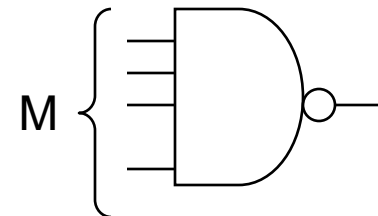
- ❑ Fan-out – number of load gates connected to the output of the driving gate

- ❑ gates with large fan-out are slower



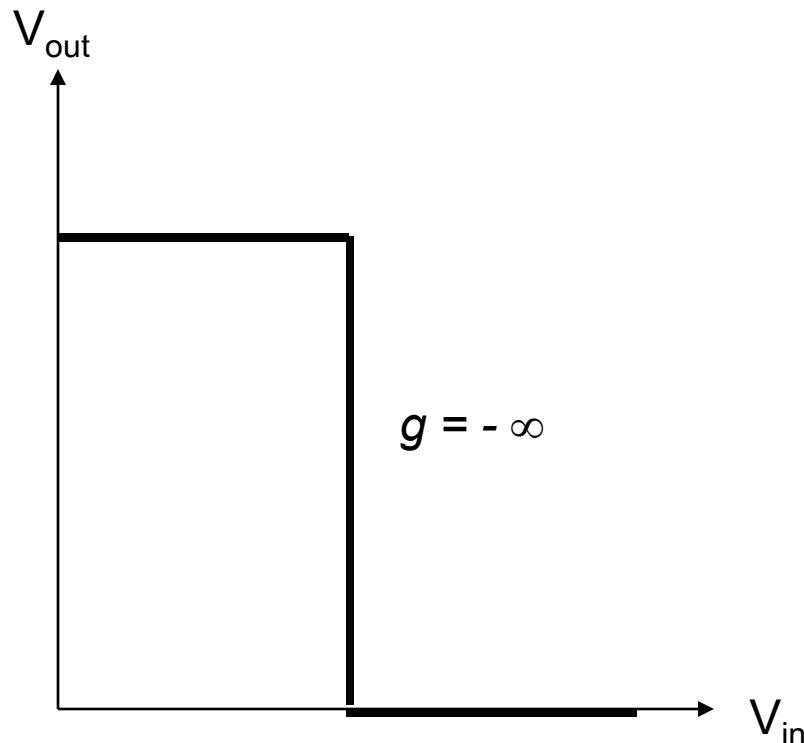
- ❑ Fan-in – the number of inputs to the gate

- ❑ gates with large fan-in are bigger and slower



The Ideal Inverter

- ❑ The ideal gate should have
 - ❑ infinite gain in the transition region
 - ❑ a gate threshold located in the middle of the logic swing
 - ❑ high and low noise margins equal to half the swing
 - ❑ input and output impedances of infinity and zero, resp.



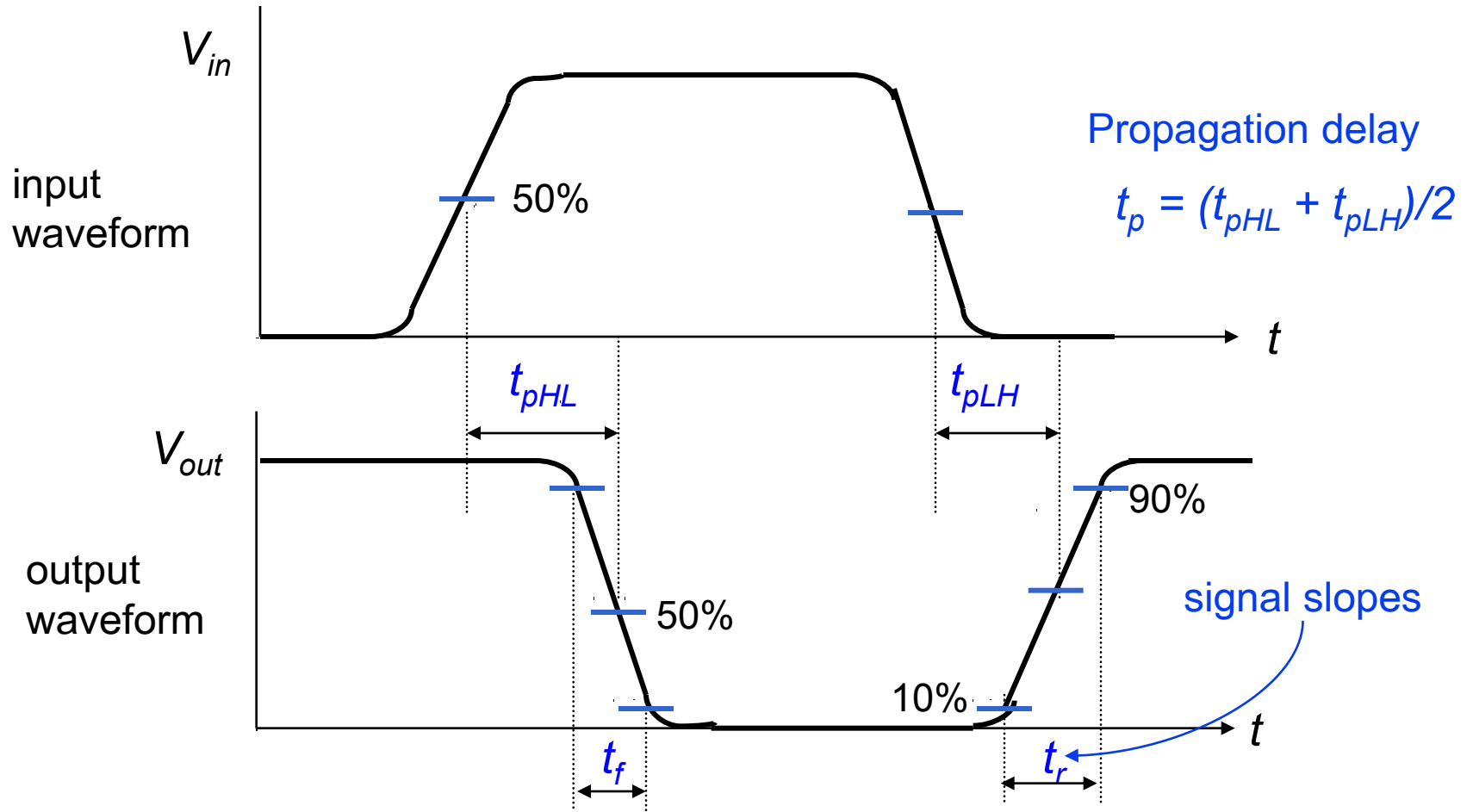
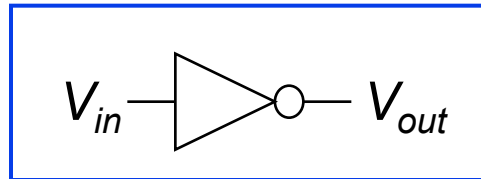
$$R_i = \infty$$

$$R_o = 0$$

$$\text{Fanout} = \infty$$

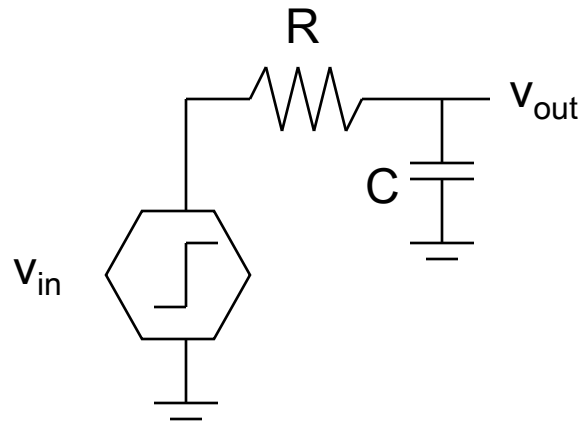
$$NM_H = NM_L = V_{DD}/2$$

Delay Definitions



Modeling Propagation Delay

- Model circuit as first-order RC network



$$v_{out}(t) = (1 - e^{-t/\tau})V$$

$$\text{where } \tau = RC$$

Time to reach 50% point is
 $t = \ln(2) \tau = 0.69 \tau$

Time to reach 90% point is
 $t = \ln(9) \tau = 2.2 \tau$

- Matches the delay of an inverter gate

Power and Energy Dissipation

- Power consumption: how much energy is consumed per operation and how much heat the circuit dissipates

- supply line sizing (determined by **peak power**)

$$P_{\text{peak}} = V_{\text{dd}} i_{\text{peak}}$$

- battery lifetime (determined by **average power dissipation**)

$$p(t) = v(t)i(t) = V_{\text{dd}}i(t) \quad P_{\text{avg}} = 1/T \int p(t) dt = V_{\text{dd}}/T \int i_{\text{dd}}(t) dt$$

- packaging and cooling requirements

- Two important components: **static** and **dynamic**

$$E \text{ (joules)} = C_L V_{\text{dd}}^2 P_{0 \rightarrow 1} + t_{\text{sc}} V_{\text{dd}} I_{\text{peak}} P_{0 \rightarrow 1} + V_{\text{dd}} I_{\text{leakage}}$$

$$\downarrow f_{0 \rightarrow 1} = P_{0 \rightarrow 1} * f_{\text{clock}} \downarrow$$

$$P \text{ (watts)} = C_L V_{\text{dd}}^2 f_{0 \rightarrow 1} + t_{\text{sc}} V_{\text{dd}} I_{\text{peak}} f_{0 \rightarrow 1} + V_{\text{dd}} I_{\text{leakage}}$$

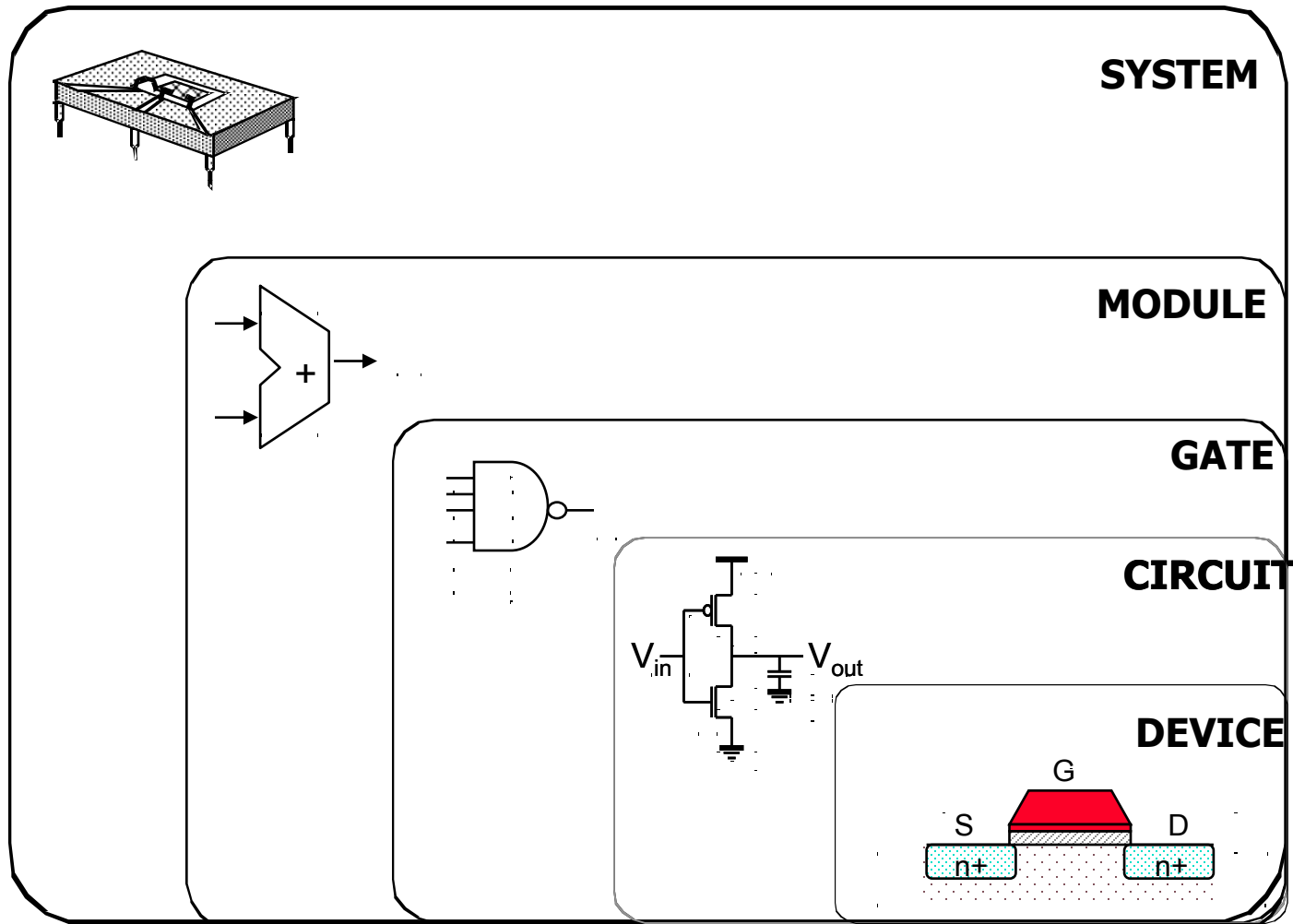
Power and Energy Dissipation

- ❑ Propagation delay and the power consumption of a gate are related
- ❑ Propagation delay is (mostly) determined by the speed at which a given amount of energy can be stored on the gate capacitors
 - ❑ the faster the energy transfer (higher power dissipation) the faster the gate
- ❑ For a given technology and gate topology, the product of the power consumption and the propagation delay is a constant
 - ❑ **Power-delay product (PDP)** – energy consumed by the gate per switching event
- ❑ An ideal gate is one that is fast and consumes little energy, so the ultimate quality metric is
 - ❑ **Energy-delay product (EDP)** = power-delay ²

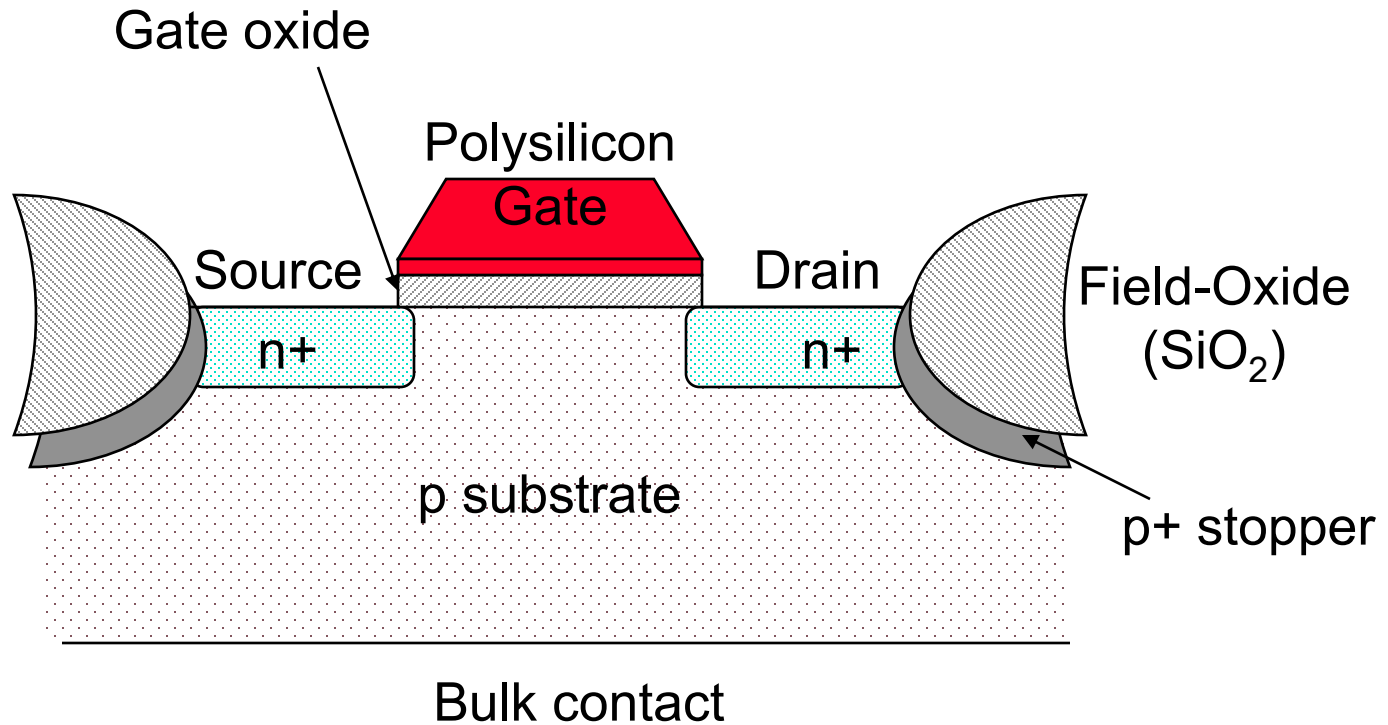
Summary

- ❑ Digital integrated circuits have come a long way and still have quite some potential left for the coming decades
- ❑ Some interesting challenges ahead
 - ❑ Getting a clear perspective on the challenges and potential solutions is the purpose of this course
- ❑ Understanding the design metrics that govern digital design is crucial
 - ❑ Cost, reliability, speed, power and energy dissipation

Design Abstraction Levels

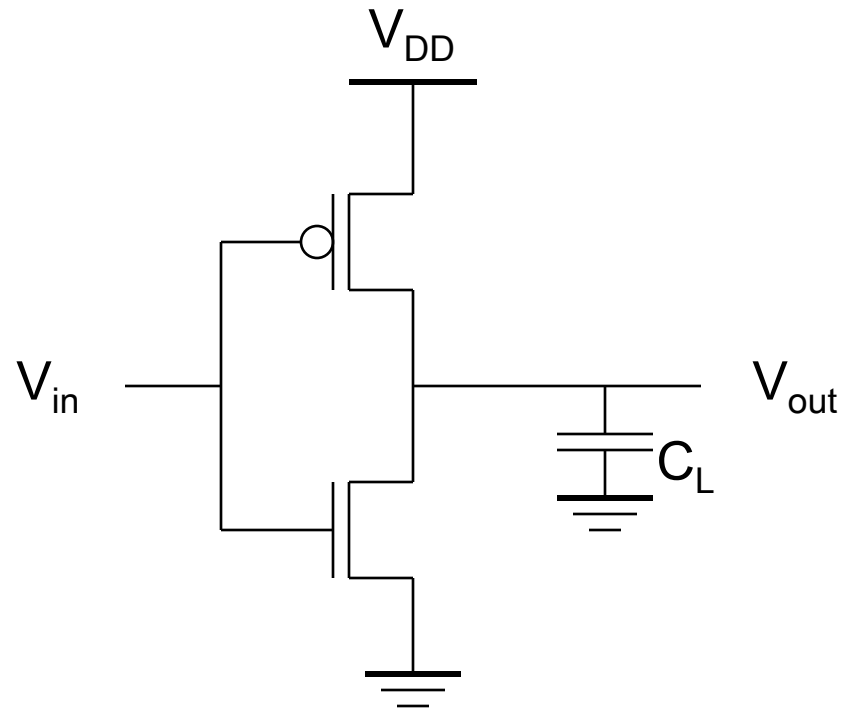


Device: The MOS Transistor



CROSS-SECTION of NMOS Transistor

Circuit: The CMOS Inverter



Next Lecture and Reminders

□ Next lecture

□ MOS transistor

- Reading assignment – Rabaey et al, 3.1-3.3.2

□ Reminders

□ Hands on max tutorial *tonight*

- Tonight in 101 Pond Lab

□ HW1 available on the web by 5:00pm

□ Project Description available on the web by 5:00pm tomorrow